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Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	863	703/6.ccls.	US-PGPUB; USPAT; EPO; DERWENT	OR	OFF	2007/02/27 16:25

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L1	46	local adj flare	US-PGPUB; USPAT; EPO; DERWENT	OR	OFF	2007/02/27 17:15
L2	4	("20030068565" "20040021854" "20040196447" "6233056").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/02/27 17:32
L3	4573	flar\$3 and mask	US-PGPUB; USPAT; EPO; DERWENT	OR	OFF	2007/02/27 17:33
L4	1367	L3 and (lithography or photolithography)	US-PGPUB; USPAT; EPO; DERWENT	OR	OFF	2007/02/27 17:35
L6	364	L4 and (OPC or correction)	US-PGPUB; USPAT; EPO; DERWENT	OR	OFF	2007/02/27 17:52
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... The LOAFLER is designed to measure the local area flare of the lens, that is, the short and mid-range flare and the **local flare** distribution of the exposure ...

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H Hata, H Nogawa, S Suda - Proceedings of SPIE, 2004 - link.aip.org
... When compared to ArF, **local flare** increases significantly. However, it has been confirmed that **local flare** can be greatly mitigated ...

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T Yao, M Osawa, T Minami, N Yamamoto, H Aoyama, G ... - VLSI Technology, 2003. Digest of Technical Papers. 2003 ..., 2003 - ieeexplore.ieee.org
Page 1. 4B-1 Local Flare Effects and Correction in ArF Lithography Teruyoshi Yao, Morimi Osawa, Takayoshi Mind , Norihiro Yamamoto, Hajime Aoyama, Genshi Okuda, ...
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LE Ericsson - AZAA Journal, 1968 - pdf.aiaa.org
... **local flare** forces become dynamically destabilizing. ... 2 and the **local "flare** efficiency" type of effects can easily be compted . It ...
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... been developed for correcting line width variations due to midrange flare with a scattering range of over a few tens of micrometers (which we call **local flare** ...
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... 4 1 at the outer edge, giving $h/r \propto r^{\alpha}$. This latter relation yields a slope of $dh/dr = 0.1$ at the outer edge of the disk, corresponding to a **local flare** angle of ...
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K Nandra, IM George, RF Mushotzky, TJ Turner, T ... - The Astrophysical Journal, 1999 - journals.uchicago.edu
... the variation in the blue wing could be due to an enhancement in the illuminating flux of the inner disk portion moving toward us, due to a **local flare** (cf. ...
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H Yoda, F Murai - US Patent 5,278,421, 1994 - Google Patents

... ACHARGED PARTICLE BEAM AND APPARATUS FOR REALIZING SAME [75] Inventors: Haruo Yoda; Fumio Murai, both of ... posed is extremely small and that the area density ...

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... , M Mizutani, T Yamamoto, H Hayashi, Y Murai - Acta Neuropathologica, 1994 - Springer

... JX Zhao - A. Ohnishi () 9 T. Yamamoto 9 Y. Murai Department of Neurology); University of ... NF per axon and per m² of the transverse axonal area (density) were cal ...

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Y Zheng, WW Lu, Q Zhu, L Qin, S Zhong, JC Leong - Spine, 2000 - spinejournal.com

... calculated from quantitative computed tomography (QCT), was used to obtain area density (g/cm²) ... Okuyama K, Sato K, Abe E, Inaba H, Shimada Y, Murai H. Stability ...

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K Takahashi, M Osawa, M Sato, H Arimoto, K Ogino, ... - Journal of Vacuum Science & Technology B: Microelectronics ..., 2000 - link.aip.org

... F. Murai, H. Yoda, S. Okazaki, N. Saitou, and Y. Sakitani, "Fast proximity effect correction method using a pattern area density map," J. Vac. Sci. ...

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F Murai, H Fukuda, S Mori, A Sato, K Nakajo - Proceedings of SPIE, 2003 - spie.org

Abstract. PUBLICATIONS. Proximity-effect correction for EPL by using multiple pattern-area-density maps and pattern classification Murai, Fumio, Hitachi, Ltd. ...

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Yao, T.; Osawa, M.; Minami, T.; Yamamoto, N.; Aoyama, H.; Okuda, G.; Sawano, T.; Kamatsuki, I.; Sugimoto, F.; Futatsuya, H.; Kobayashi, K.; Ogino, K.; Hoshino, H.; Machida, Y.; Arimoto, H.; Asai, S.; [VLSI Technology, 2003. Digest of Technical Papers, 2003 Symposium on](#)
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V Singhal, CB Keshav, KG Sumanth, PR Suresh - Design Automation Conference, 2002. Proceedings of ASP-DAC ..., 2002 - ieeexplore.ieee.org
... 4.1 Designing out flares- A solution for high ... Our analysis with statistical simulation results showed that we ... Most OPC based corrective schemes, which involve ...

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M Fritze, RD Mallen, B Wheeler, D Yost, JP Snyder, ... - Proceedings of SPIE, 2003 - photonics.com
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TB Chiou, S Hsu, M Eurlings, E Hendrickx, A Chen - Microprocesses and Nanotechnology Conference, 2004. Digest ..., 2004 - ieeexplore.ieee.org
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HC Kim, DS Nam, GS Yeo, SJ Lee, SG Woo, HK Cho, WS ... - Proceedings of SPIE, 2004 - link.aip.org
... scattering range characteristic of flare. To minimize CD errors from OPC, flare level and EOR should be considered in the OPC procedure. ...
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M Chandhok, SH Lee, CG Krautschik, G Zhang, BJ ... - Proceedings of SPIE, 2004 - spie.org
... expected that to meet the CD control requirements for the 32 nm node, Flare Variation Compensation (FVC), akin to Optical Proximity Correction (OPC) would be ...
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... and horizontal mask patterns and application of OPC techniques as ... The percentage of flare was calculated using the following equation: Straylight % = E_0 ...
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TA Brunner, N Seong, WD Hinsberg, JA Hoffnagle, FA ... - Journal of Microlithography, Microfabrication, and ..., 2002 - link.aip.org
... by the pupil edge, defocus effects, image flare effects, stage ... mask will need more accurate calculation than that ... for optical proximity correction (OPC) methods ...
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Sang Hun Lee, Manish Chandhok, Christof Krautschik, and Michael Goldstein
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Yorick Trouiller, Emmanuelle Luce, Alexandra Barberet, L. Depre, and Patrick Schiavone
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Hiroki Futatsuya, Teruyoshi Yao, Morimi Osawa, Kozo Ogino, Hiromi Hoshino, Hiroshi Arimoto, Yasuhide Machida, and Satoru Asai
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